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PATENT
Attorney Docket No.: 016301-035000US
Client Ref. No.: A4467/T35000

Assistant Commissioner for Patents
Washington, D.C. 20231

On July 1, 2002

TOWNSEND and TOWNSEND and CREW LLP

By: 

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Technology Center 2100

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Christopher Ngai, et al.

Application No.: 09/759,854

Filed: January 12, 2001

For: NITROGEN DOPING OF FSG
LAYER

Examiner: Unassigned

Art Unit: 2812

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination of the above-referenced application, please enter the following amendments and remarks.

IN THE CLAIMS:

Please amend claims 1-3, 14, 17, 26, and 29 as follows. The remaining claims are unamended, but are reproduced below for the Examiner's convenience and reference.

1. (Amended) A method for depositing a layer on a substrate in a process chamber, the method comprising:

Claims 1-28 2823 OK by OTK Chaudhuri 10-Dec-02
29-30 2125 OK WKS

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